

Feature

- Precision MEMS process
- High performance, shielded, Micro-cavity structure
- Silicon substrate, 50Ω CPW output
- Au wire bonding, for MCM applications

Environmental Specifications

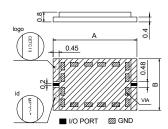
Operating Temperature	-55℃~+85℃	
Storage Temperature	-55°C∼+125°C	
Max. Input Power	35dBm	

Electrical Specifications(T_A=+25°C)

Parameter	Min.	Тур.	Max.	Unit
Center Freq. (f₀)	-	28.5	-	GHz
Pass Band	25.6	-	31	GHz
Ripple in Pass band	-	-	1	dB
Insertion Loss @ fo	-	-	1.1	dB
Return Loss	15	-	-	dB
Out of band	≥20@23	dB		
	≥40@22	dB		
Attenuation	≥60@DC~8.9GHz			dB
Group Delay Variation	≤0.3@25.6~31GHz			ns
Linear Phase	≤±13@25.6~31GHz			0

S2P file name: SiMF28R5_5-5W2.s2p

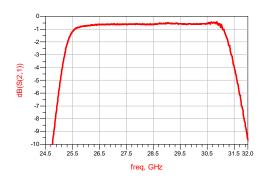
Outline Drawing



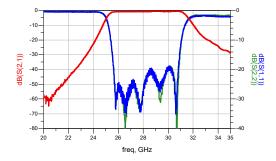
	Symbol	Value (mm)		
		Min.	Nominal	Max.
	А	9.5	-	9.6
	В	3.5	-	3.6

Typical Test Curves

Insertion Loss VS Frequency (T_A=25°C)



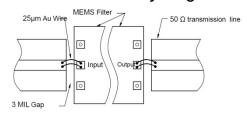
Insertion Loss & Return Loss VS Frequency (T_A=25°C)



Broadband Insertion Loss VS Frequency (T_A=25°C)

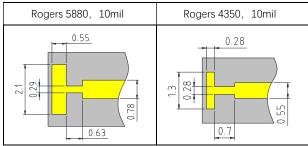


Recommended Assembly Diagrams



Application Notes:

- 1. The chip is back-metalized and can be die mounted with AuSn eutectic performs or with electrically conductive epoxy (for example ME8456).
- 2. The die should be assembled on carriers like Kovar or Mu-Cu which have same Coefficient of thermal expansion. (2.9ppm/°C) with Silicon, thickness 0.2mm max.
- 3. Handle the chips in a clean environment. DO NOT attempt to clean the chip using liquid cleaning systems.
- 4. Handle the chip along the edges with a vacuum collet or with a sharp pair of bent tweezers.
- 5. Recommended to use T structure as below for bonding.



6. If you have any questions, please contact us.